



Attorney Docket No. 1081.1137

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of:

Yoshimasa IIDUKA et al.

Application No.: 10/073,246

ATTENTION

Confirmation No.: 4438

CERTIFICATE OF CORRECTION

Filed: February 13, 2002

BRANCH

U.S. Patent No.: 6,968,531

Issued: November 22, 2005

For: EXPOSURE METHOD UTILIZING OPTICAL PROXIMITY CORRECTED EXPOSURE PATTERNS, AN APPARATUS FOR GENERATING OPTICAL PROXIMITY CORRECTED EXPOSURE DATA, AND AN EXPOSURE APPARATUS FOR OPTICAL PROXIMITY CORRECTED EXPOSURE DATA

REQUEST FOR CERTIFICATE OF CORRECTION

Commissioner for Patents
PO Box 1450
Alexandria, VA 22313-1450

Certificate
SEP 29 2006
of Correction

Sir:

Patentee(s) respectfully request(s) that a Certificate of Correction be issued in the subject patent, pursuant to 35 U.S.C. §254 and 37 C.F.R. §1.322, to correct the mistake(s) shown on the attached Form PTO-1050.

Since the mistakes are Patent Office mistakes, it is believed that no fee is required.

Respectfully submitted,

STAAS & HALSEY LLP

Date:

September 27, 2007

By:

David M. Pitcher

David M. Pitcher
Registration No. 25,908

1201 New York Ave, N.W., 7th Floor
Washington, D.C. 20005
Telephone: (202) 434-1500
Facsimile: (202) 434-1501

SEP 03 2006

UNITED STATES PATENT AND TRADEMARK OFFICE

CERTIFICATE OF CORRECTION

PATENT NO : 6,968,531

DATED : November 22, 2005

INVENTOR(S) : Yoshimasa IIDUKA et al.

Column 9, Line 56, delete "where" and insert -- wherein -- therefor.
Column 9, Line 57, after "optical" insert -- proximity --.
Column 10, Line 2, after "data" insert -- at --.
Column 10, Line 5, delete "exposed" and insert -- exposure -- therefor.
Column 10, Line 8, delete "optical" and insert -- optional -- therefor.
Column 10, Line 10, after second occurrence of "exposure" insert -- pattern --.
Column 10, Line 11, delete "optical" and insert -- optional -- therefor.
Column 10, Line 17, after "data" insert -- is expected to be less than that of the minus objective pattern data and the minus pattern data --.
Column 10, Line 18, delete "optical" and insert -- optional -- therefor.
Column 10, Line 21, delete "exposed" and insert -- expected -- therefor.
Column 10, Line 22, delete "optical" and insert -- optional -- therefor.
Column 10, Line 24, after "bitmapped" insert -- pattern --.
Column 10, Line 26, delete "th" and insert -- the -- therefor.
Column 10, Line 31, delete "where" and insert -- wherein -- therefor.
Column 10, Line 45, after "data" insert -- at --.
Column 10, Line 51, delete "optical" and insert -- optional -- therefor.
Column 10, Line 53, after "divided exposure" insert -- pattern --.
Column 10, Line 54, delete "optical" and insert -- optional -- therefor.
Column 10, Line 62, after "minus" insert -- objective --.
Column 10, Line 63, delete "optical" and insert -- optional -- therefor.
Column 10, Line 65, after "of the" insert -- minus objective pattern data and the minus pattern data is expected to be less than that of the --.
Column 10, Line 66, delete "optical" and insert -- optional -- therefor.
Column 11, Line 7, delete "side" and insert -- sides --.
Column 11, Line 15, after "data" insert -- at --.
Column 11, Line 17, delete "apparatus" and insert -- method -- therefor.
Column 11, Lines 19-20, after "data" delete ", to generate corrected exposure pattern data, the apparatus" and insert -- and exposes a substrate in accordance with bitmapped pattern data, the method -- therefor.
Column 11, Line 24, after "exposure" insert -- pattern --.
Column 12, Line 3, after "minus" insert -- objective --.
Column 12, Line 3, after "wherein" insert -- an area corresponding to the minus pattern data is included in an area corresponding to --.
Column 12, Line 14, delete "side" and insert -- sides -- therefor.
Column 12, Line 16, delete "claim 7" and insert -- claim 10 -- therefor.
Column 12, Line 22, after "data" insert -- at --.

MAILING ADDRESS OF SENDER:

STAAS & HALSEY LLP
1201 New York Ave., N.W.
7th Floor
Washington, DC 20005

PATENT NO. 6,968,531

No. of add'l copies
@ 50¢ per page

⇒

